

**Application Data Sheet****Applicant Information**

Applicant Authority type::	Inventor
Primary Citizenship Country::	Japan
Status::	Full Capacity
Given Name::	Syo-ichi
Family Name::	TAKAMIZAWA
City of Residence::	Annaka-shi
Country of Residence::	JAPAN

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Applicant Authority Type::	Inventor
Primary Citizenship Country::	Japan
Status::	Full Capacity
Given Name::	Ryuji
Family Name::	SAYAMA
City of Residence::	Annaka-shi
Country of Residence::	JAPAN

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**Correspondence Information**

Correspondence Customer Number::	25944
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**Application Information**

Application Type::	National Phase
Subject Matter::	Utility
CD-ROM or CD-R::	None
Title::	METHOD FOR PRODUCING SILICON EPITAXIAL WAFER
Attorney Docket Number::	127101
Suggested Drawing Figure::	1
Total Drawing Sheets::	2
Small Entity::	No

**Representative Information**

Attorneys associated with Customer No. 25944.

<b>Domestic Priority Information</b>			
Application::	Continuity Type::	Parent Application::	Parent Filing Date::
This Application is a	National Stage of	PCT/2004/012179	8/25/2004
<b>Foreign Priority Information</b>			
Country::	Application Number::	Filing Date::	Priority Claimed::
JAPAN	2003-385333	11/14/2003	Yes
<b>Assignee Information</b>			
Assignee Name::		SHIN-ETSU HANDOTAI CO., LTD.	
Street of mailing address::		4-2, MARUNOUCHI 1-CHOME, CHIYODA-KU,	
City of mailing address::		TOKYO	
Country of mailing address::		JAPAN	
Postal or Zip Code of mailing address::		100-0005	